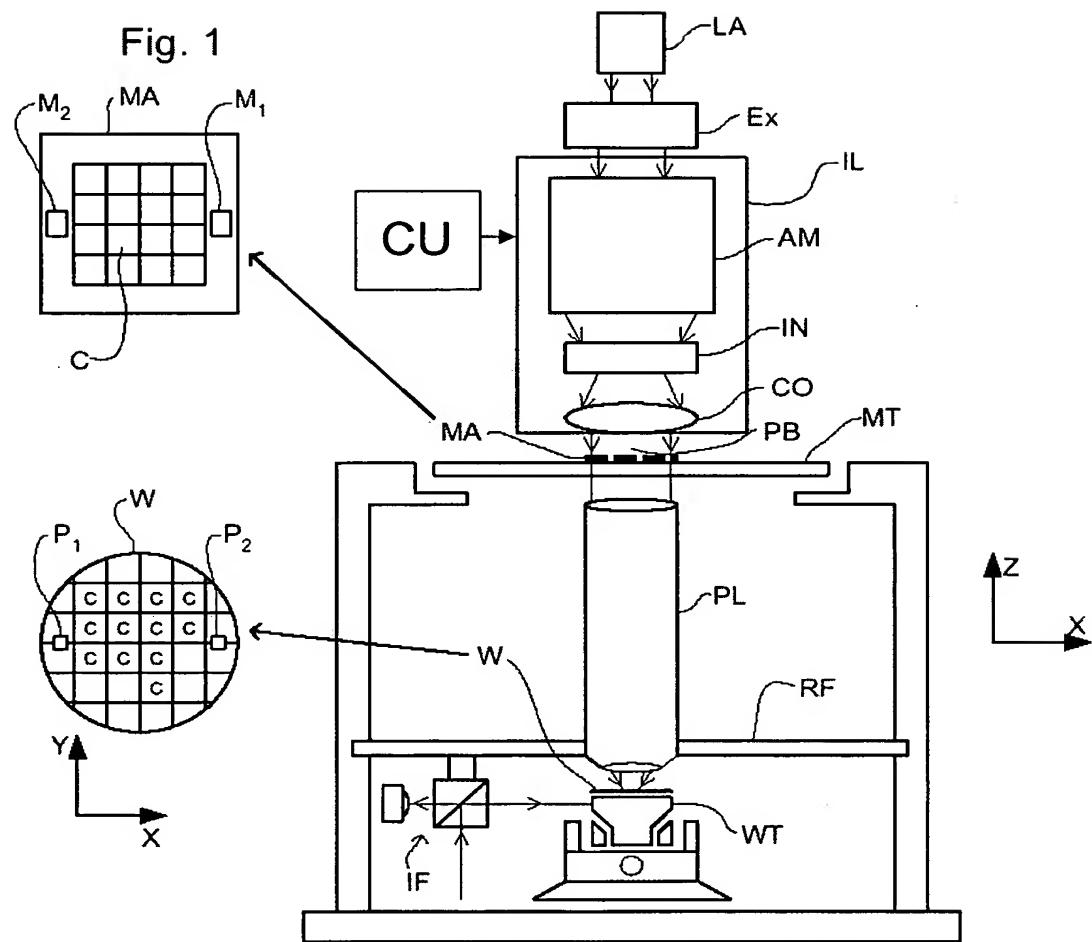


Fig. 1



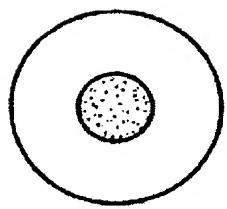


FIG. 2

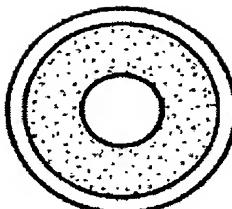


FIG. 3

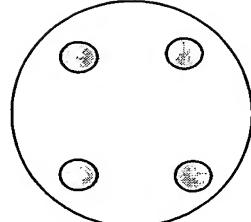


FIG. 4

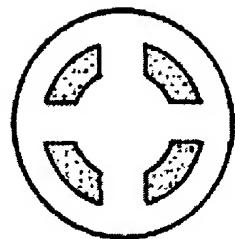


FIG. 5

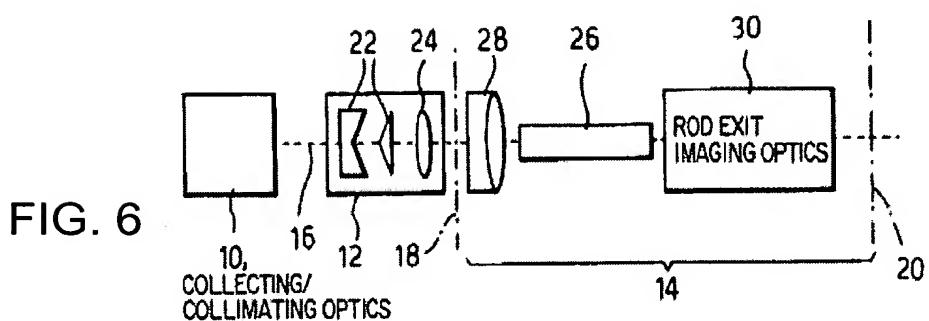


FIG. 6

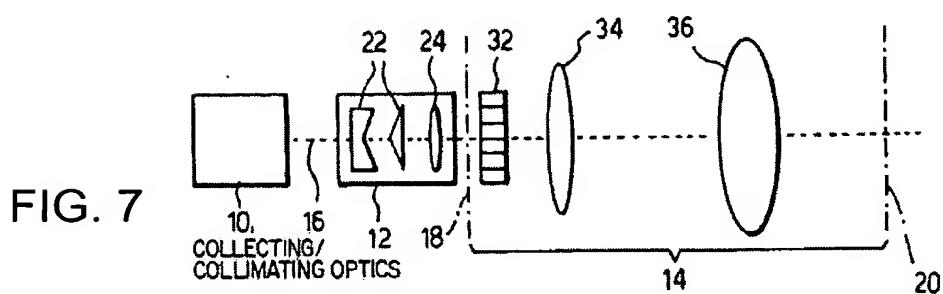
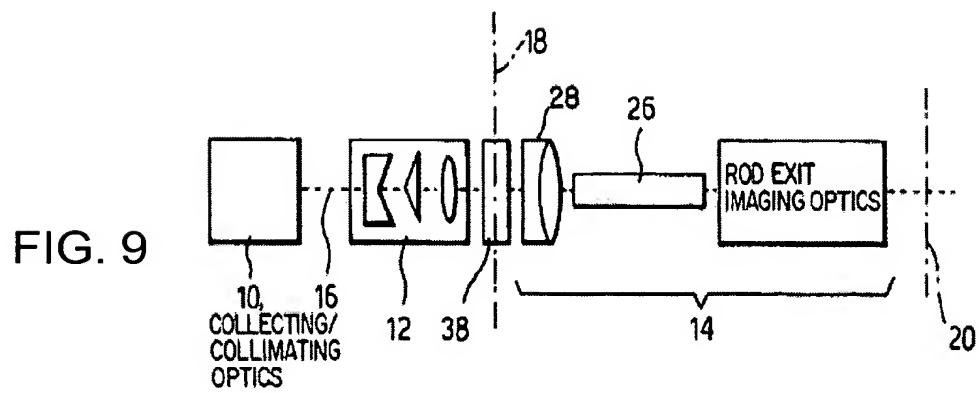
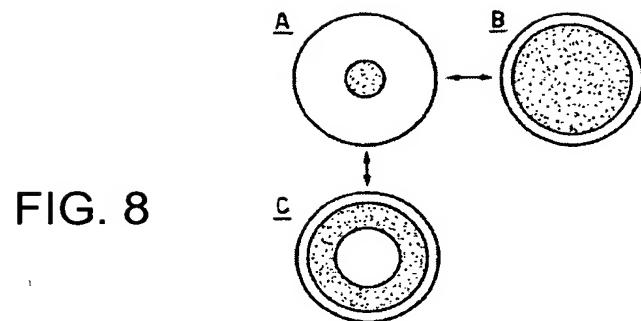


FIG. 7



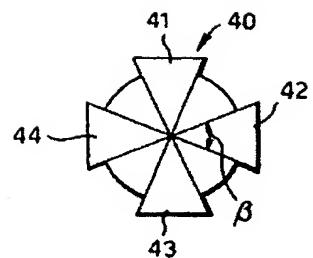


FIG. 10a

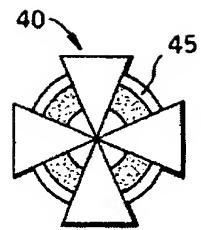


FIG. 10b

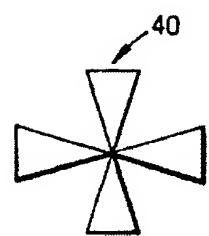
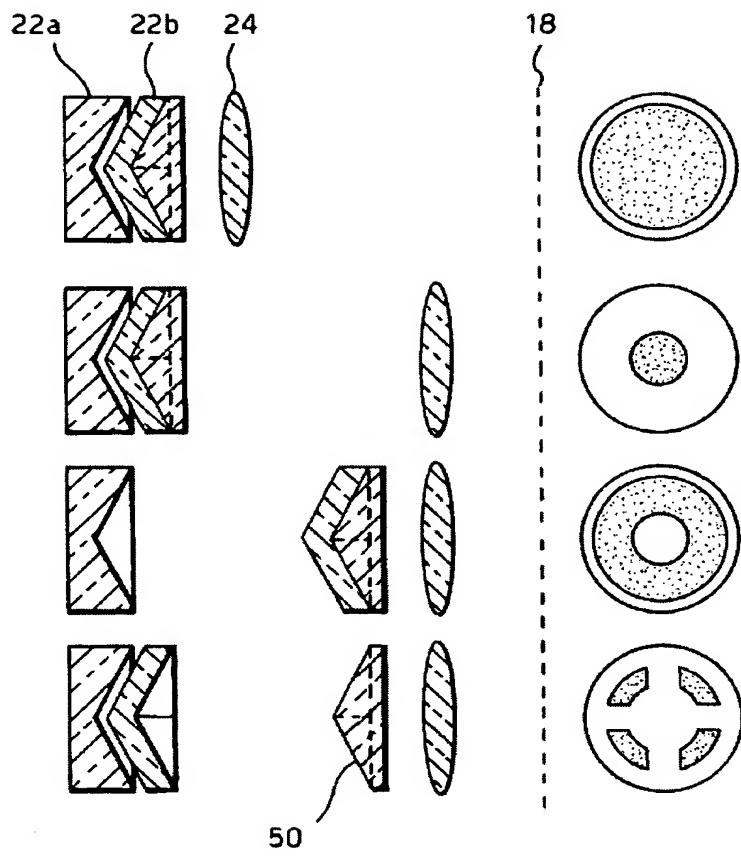


FIG. 11



**FIG. 12**

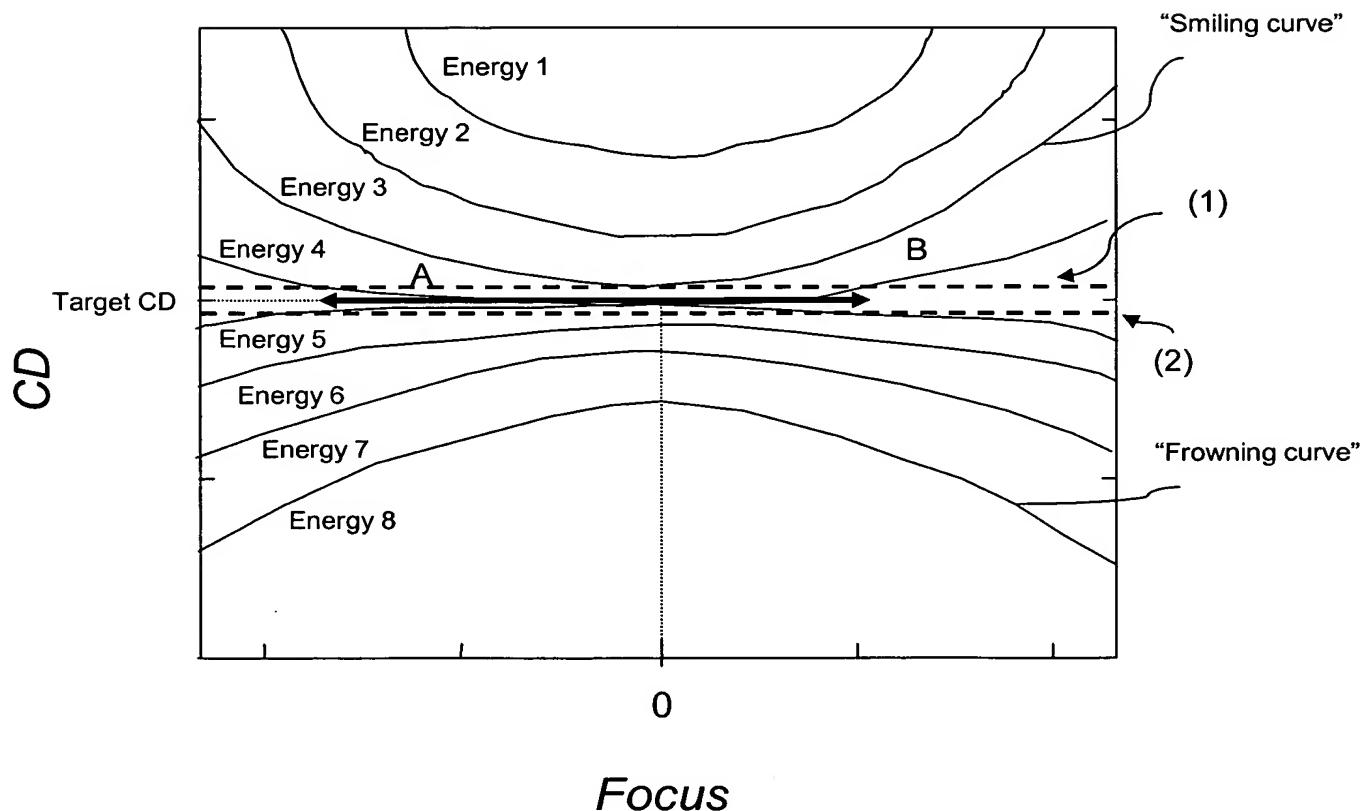


FIG. 13

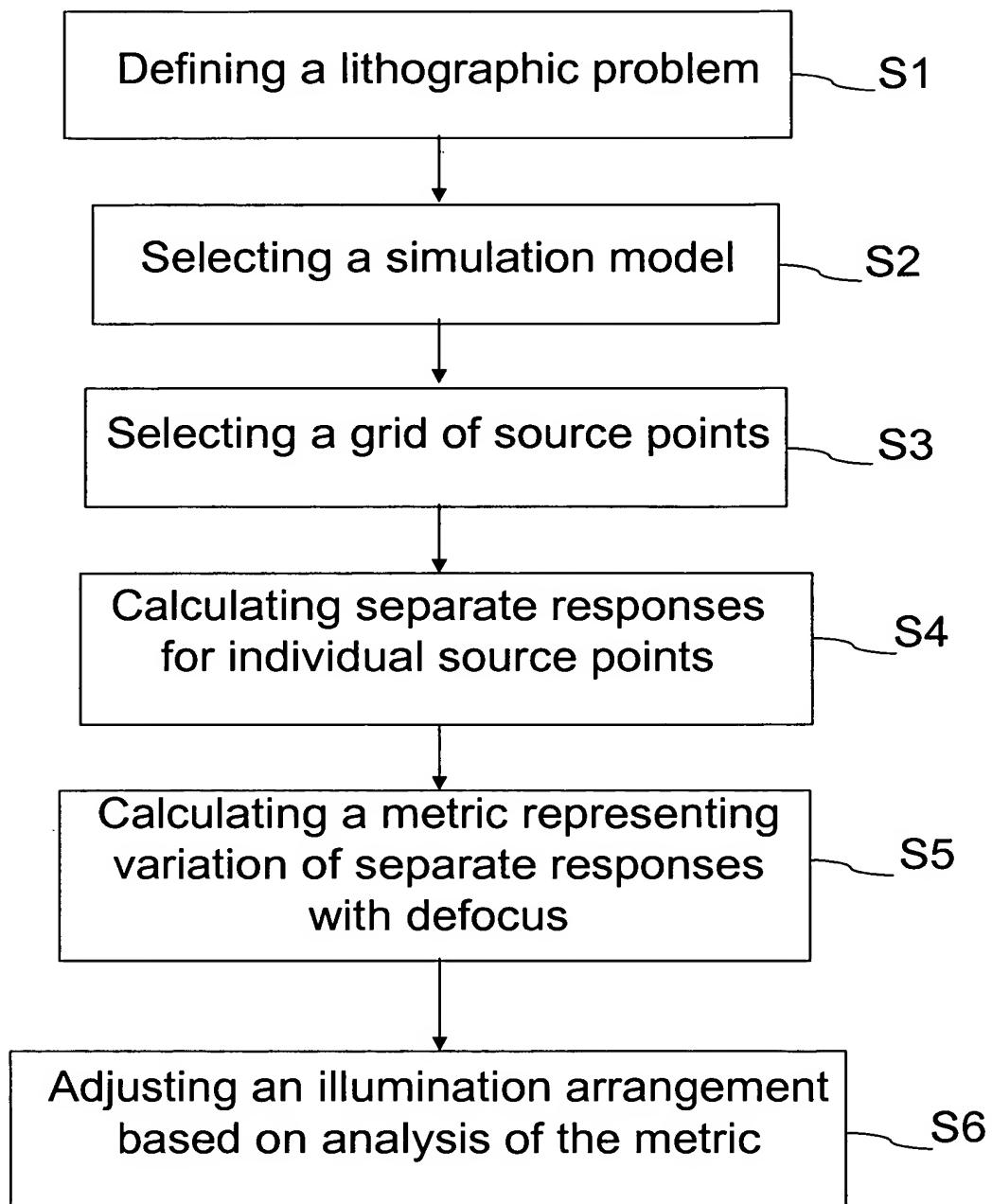


FIG. 14

FIG. 15a

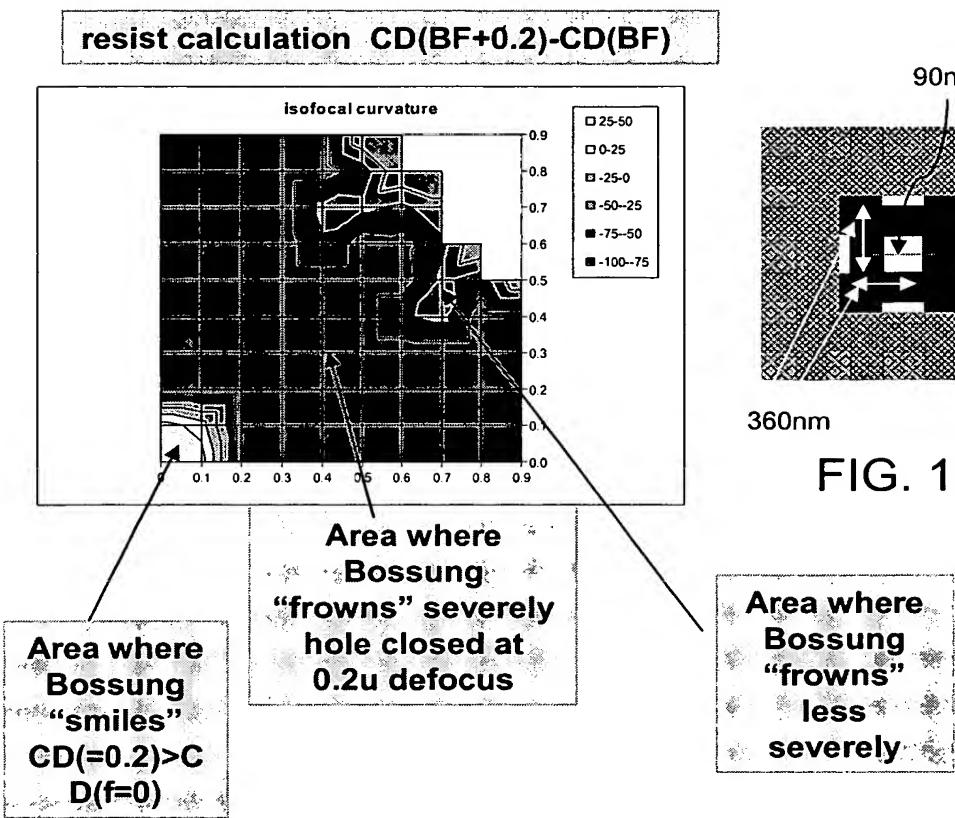
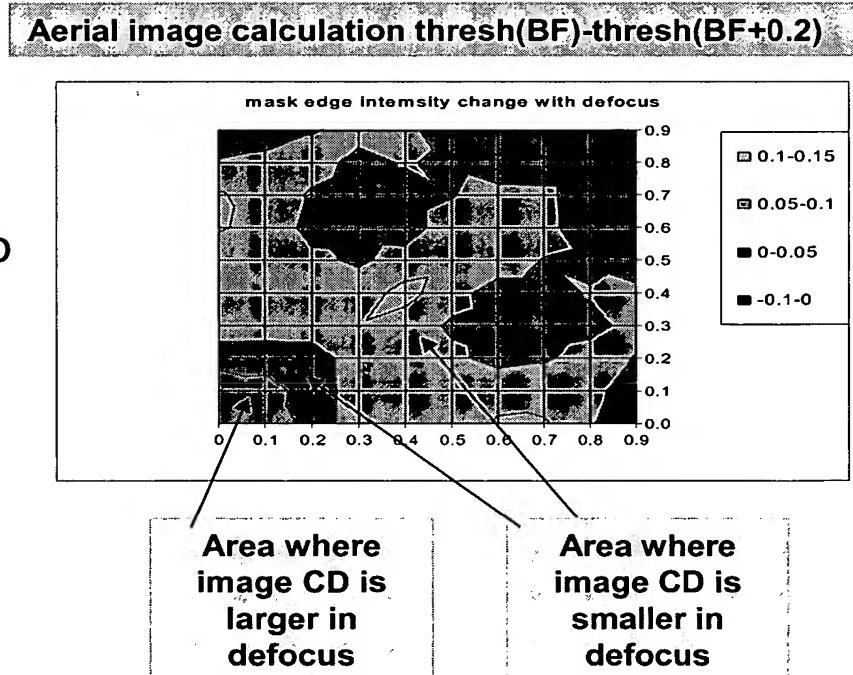


FIG. 15c

FIG. 15b



**resist calculation CD(BF+0.2)-CD(BF)**

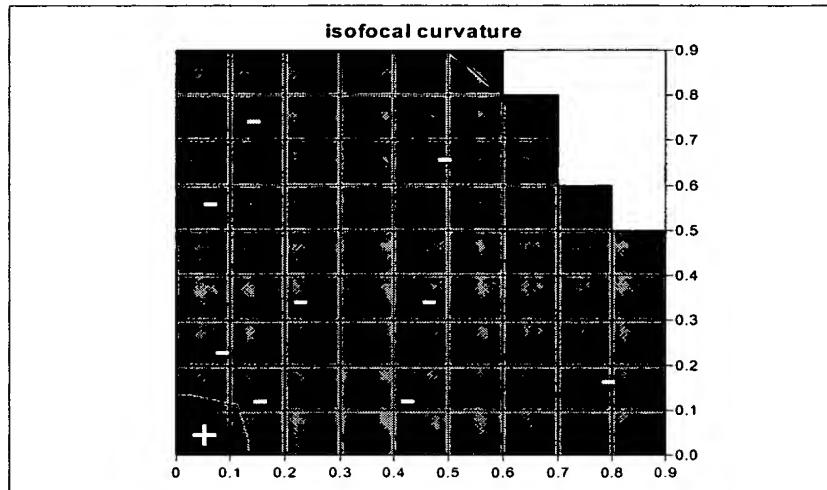


FIG. 16a

**Aerial image calculation thresh(BF)-thresh(BF+0.2)**

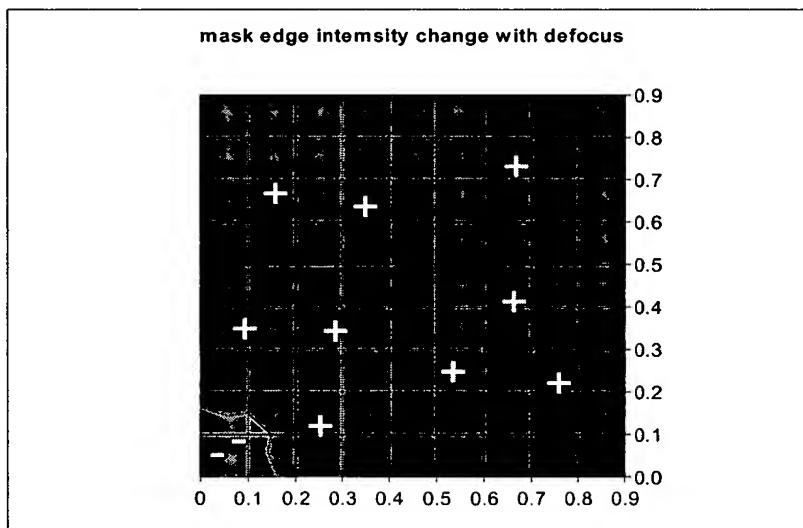
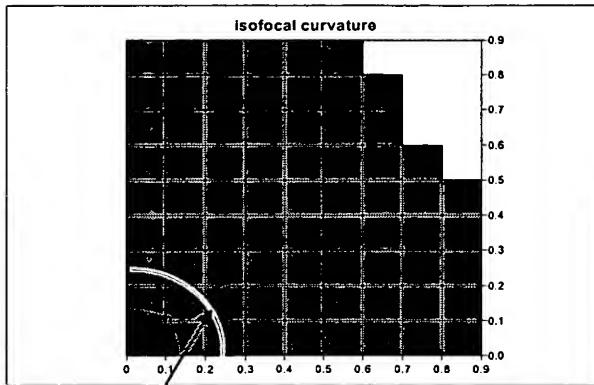


FIG. 16b

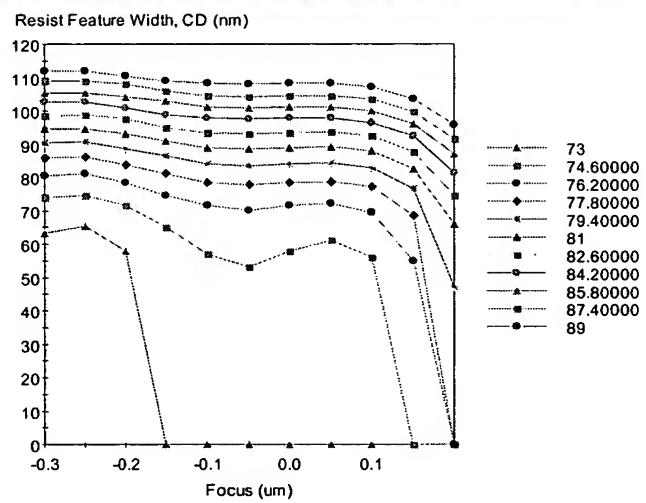
FIG. 17



$\sigma=0.25$  combines areas of + and - isofocal curvature

At  $\sigma=0.25$ , process is approximately isofocal.  
DOF is good but dose latitude is low.

FIG. 18



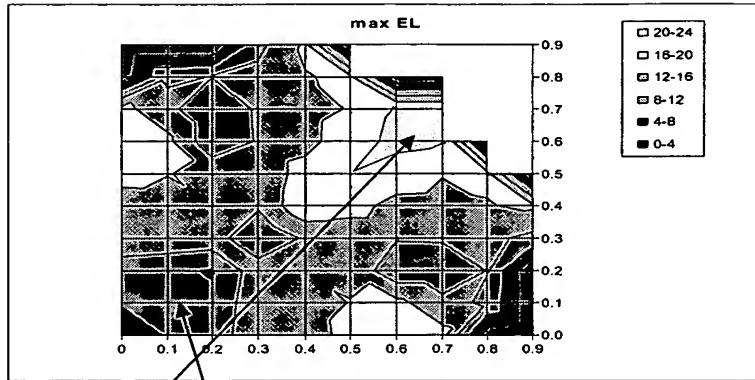


FIG. 19a

**Desirable area for high EL is wide quasar**

**Low σ area provides poor EL and also requires high dose to print (weak aerial image)**

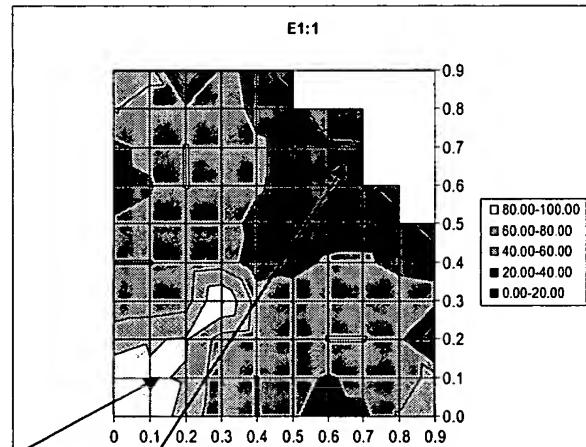


FIG. 19b

**Low σ area provides poor EL and also requires high dose to print (weak aerial image)**

**Wide quasar also provides low E1:1 (strong aerial image)**

$$\text{Illuminator} = \sigma(0.1 \text{ conv}) + (0.92/0.88Q5^\circ)$$

FIG. 20

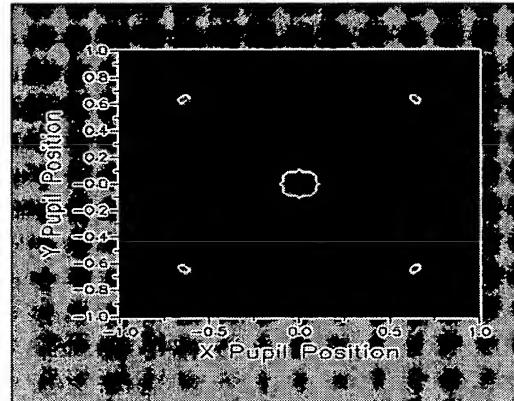


FIG. 21

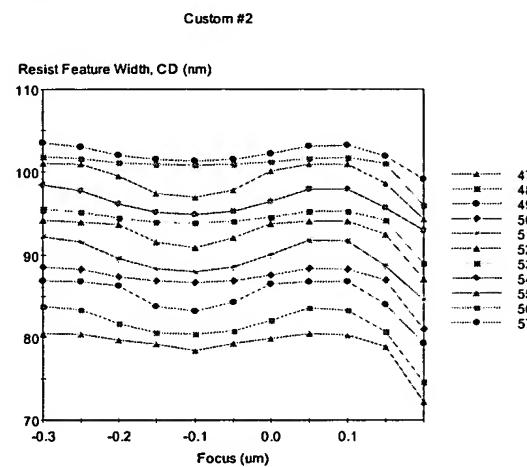
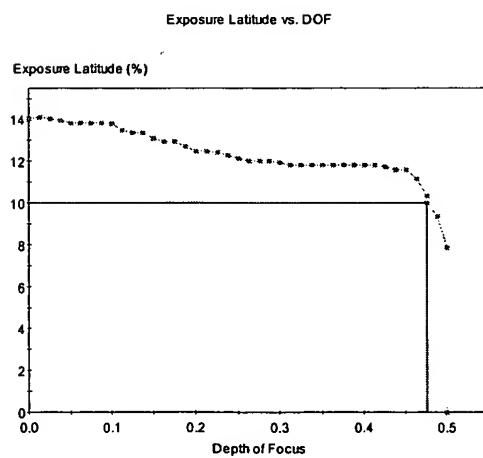


FIG. 22



optimization method	illumination	max EL	max DOF	DOF @ 10% EL	DOF @ 5% EL
standard	0.95/0.70Q30°	18%	0.3	0.18	0.24
simple isofocal compensation	0.25 conv	8%	>0.55	0	0.29
high EL isofocal compensation	0.92/0.88Q5°+0.1conv	16%	>0.65	0.57	0.63

FIG. 23

Large improvement in process window may be possible by appropriate use of illuminator to compensate isofocal curvature

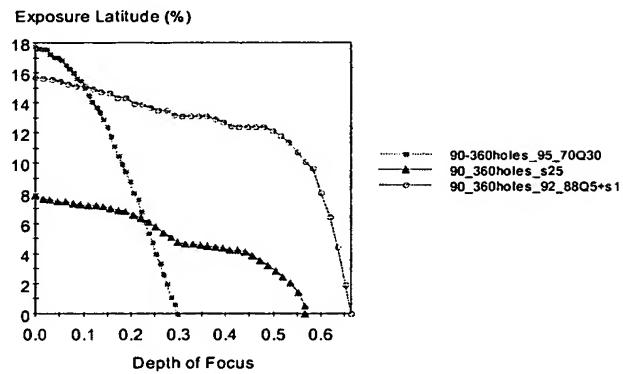


FIG. 24a

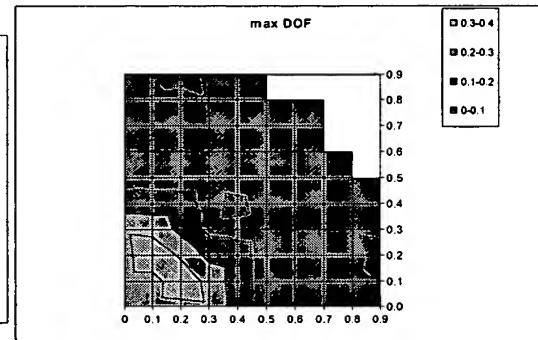
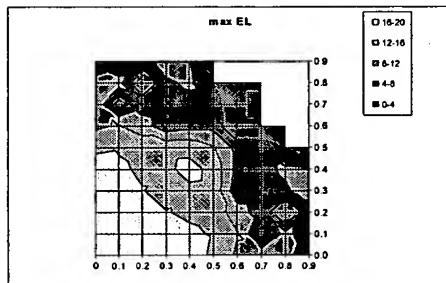


FIG. 24b

FIG. 24d

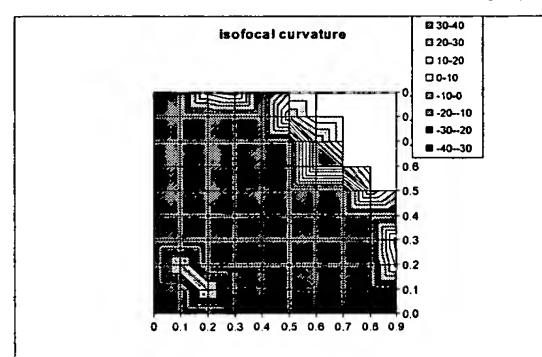
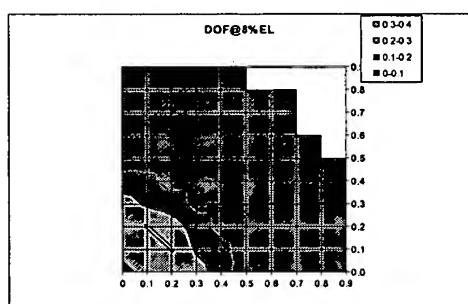


FIG. 24c

FIG. 25a

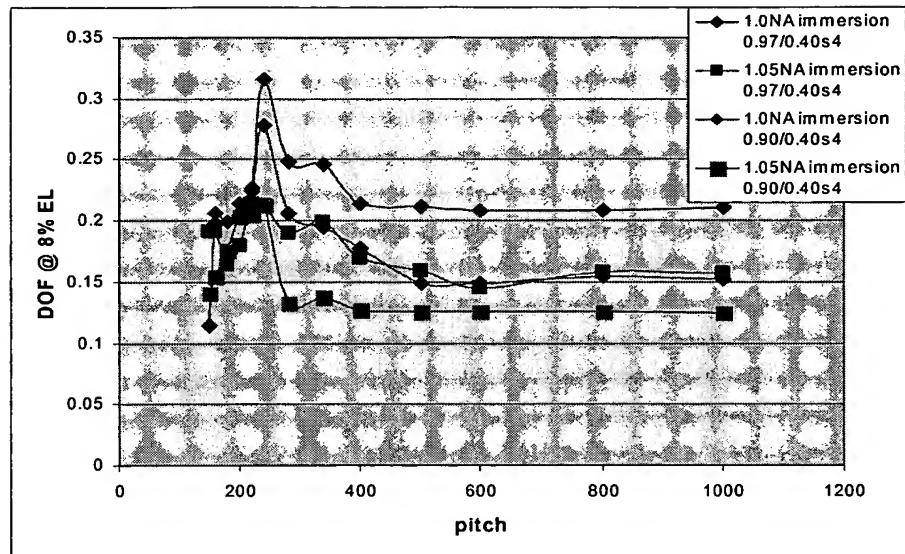
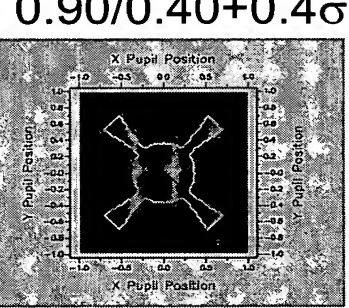


FIG. 25b



$0.90/0.40+0.4\sigma$

$0.97/0.40+0.4\sigma$

FIG. 25c

